

**FAST RECOVERY DIODES**

- Junction Size: Square 180 mils
- Wafer Size: 4"
- $V_{RRM}$  Class: 1000 and 1200 V
- Passivation Process: Glassivated MOAT
- Reference IR Packaged Part: 20ETF Series

Major Ratings and Characteristics

Parameters	Units	Test Conditions
$V_{FM}$ Maximum Forward Voltage	1350mV	$T_J = 25^\circ\text{C}$ , $I_F = 20\text{ A}$
$V_{RRM}$ Reverse Breakdown Voltage Range	1000 and 1200V	$T_J = 25^\circ\text{C}$ , $I_{RRM} = 100\ \mu\text{A}$ (1)

(1) Nitrogen flow on die edge.

Mechanical Characteristics

Nominal Back Metal Composition, Thickness	Cr - Ni - Ag (1 KA - 4 KA - 6 KA)
Nominal Front Metal Composition, Thickness	100% Al, (20 $\mu\text{m}$ )
Chip Dimensions	180 x 180 mils (4.57x4.57 mm) - see drawing
Wafer Diameter	100 mm, with std. < 110 > flat
Wafer Thickness	260 $\mu\text{m}$
Maximum Width of Sawing Line	45 $\mu\text{m}$
Reject Ink Dot Size	0.25 mm diameter minimum
Ink Dot Location	See drawing
Recommended Storage Environment	Storage in original container, in dessicated nitrogen, with no contamination

# IR180LM..CS05CB Series

Bulletin I0125J 07/97

International  
**IR** Rectifier

## Ordering Information Table

Device Code							
IR	180	L	M	12	C	S05	CB
①	②	③	④	⑤	⑥	⑦	⑧

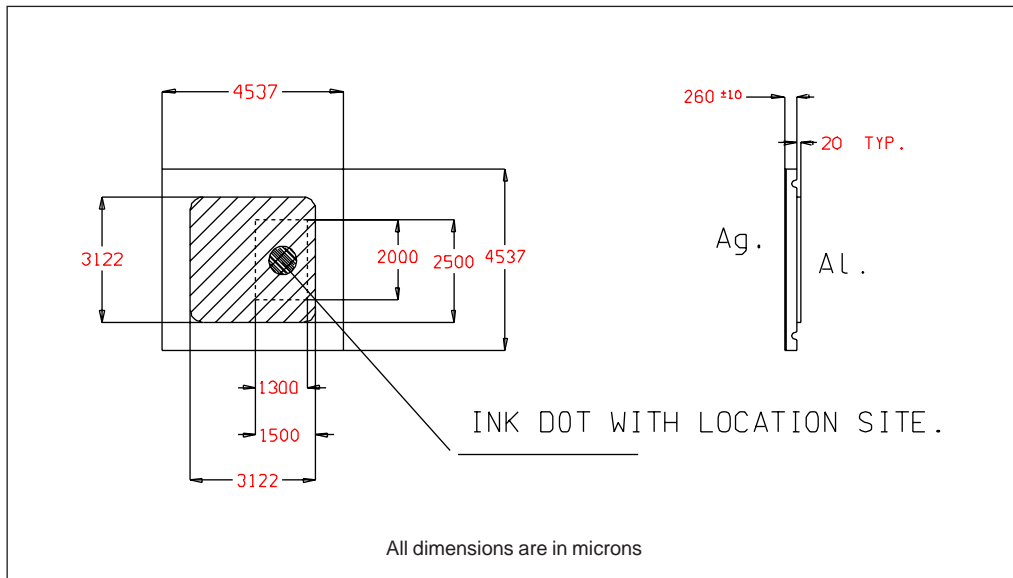
- 1** - International Rectifier Device
- 2** - Chip Dimension in Mils
- 3** - Type of Device: L = Wire Bondable Fast Recovery Diode
- 4** - Passivation Process: M = Glassivated MOAT
- 5** - Voltage code: Code x 100 =  $V_{RRM}$
- 6** - Metallization: C = Aluminium (Anode) - Silver (Cathode)
- 7** - Fast Recovery Type: S05 = 500 nsec
- 8** - CB = Probed Uncut Die (wafer in box)  
None = Probed Die in chip carrier

**Available Class**

10 = 1000 V

12 = 1200 V

## Outline Table



## Wafer Layout

